

Symposium R: Fundamentals and applications of plasma processing of materials

Scope of the Symposium

The aim of this symposium is to bring together physicists, chemists, materials scientists, dentists, engineers and members of other scientific communities, offering a forum for discussions on the advances of plasma processing of materials, from both experimental and theorical approaches, to facilitate the contacts between science, technology and industry. Areas of particular interest will include, but will not be limited to: Fundamentals of deposition processes and techniques Experiments and simulations on plasma surface-interactions Plasma characterization Plasma Enhanced Chemical Vapor Deposition of protective coatings Plasma treatment of biomaterials Surface engineering via plasma processing Applications of plasmas in agriculture, medicine and environmental sciences.

Abstracts will be solicited in (but not limited to) the following areas

• Plasma-surface interactions, PECVD, plasma polymerization, plasma immersion ion implantation and deposition, plasma etching and sputtering, plasma electrolytic oxidation, Applications of plasmas in industry, agriculture and medicine, corona treatments

Tentative list of invited speakers (To be confirmed)

Francesco Fracassi (Dipartimento di Chimica, Universit degli Studi di Bari) .

Symposium Organizers

Elidiane C Rangel (Laboratory of Technological Plasmas - Unesp) Nilson C Cruz (Laboratory of Technological Plasmas - Unesp) Clodomiro Alves Jr. (UFERSA - Department of Natural and Mathematical Sciences) Rodrigo Savio Pessoa (Instituto Tecnolgico de Aeronutica) Andr Paulo Tschiptschin (Escola Politcnica da Universidade de So Paulo) Lucia Vieira (Universidade do Vale do Paraba)

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XVIII Brazil MRS Meeting